



FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		DOCKET 001945 USA P02/ETCH/SILICON/JB				APPLICATION NO 09/362,924	
INFORMATION DISCLOSURE STATEMENT IN AN APPLICATION (Use several sheets if necessary)		APPLICANT CHOW et al				GROUP ART UNIT 1746 <u>1763</u>	
		FILING DATE 07/27/1999					
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
<i>AWO</i>	5,259,923	11/9/1993	HORI et al.	156	643		
	5,384,009	1/24/1995	MAK et al.	156	662		
	4,992,134	2/12/1991	GUPTA et al.	156	628		
	5,716,495	2/10/1998	BUTTERBAUGH et al.	156	643.1		
	5,605,601	2/25/1997	KAWASAKI	156	643.1		
	6,125,859	10/3/2000	KAO et al.	134	001.1		
<i>AWO</i>	5,861,233	1/19/1999	SEKINE et al.	430	296		
FOREIGN PATENT DOCUMENTS							
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	ABSTRACT YES NO	
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)							
<i>AWO</i>	Kimizuka, Masakatsu et al. "Pattern Profile Control in Magnetron reactive ion etching of Poly-Si." J. Vac. Sci. Technol. B 10(5), Sept/Oct 1992. pp. 2192-2196.						
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EXAMINER: <i>Allen W. Olson</i>				DATE CONSIDERED: <i>4/9/03</i>			
EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							